

ABSTRACT OF THE DISCLOSURE

Provided are an adamantane derivative characterized by having a structure represented by Formula (I) and a process for producing an adamantane derivative in which n is 0 in Formula (I) described above, wherein an adamantane compound is reacted with a nitrile compound and then with acid halide or acid anhydride of (meth)acrylic acids. The adamantane derivative characterized by having a structure represented by Formula (I) is a novel adamantane derivative which is useful as a monomer for functional resins such as a photosensitive resin in the photolithography field, and it can efficiently be produced by the production process described above.

